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**(54) Title (EN):** OPTICAL STACK

**(54) Title (FR):** EMPILEMENT OPTIQUE

**(54) Title (KO):** 광학 적층체

**(57) Abstract:**

**(EN):** The present invention relates to an optical stack or an anti-redshift layer. The present invention can provide an optical stack or an anti-redshift layer applied thereto, wherein the so-called redshift phenomenon is not induced even when the optical stack is driven or maintained under extremely harsh conditions (for example, extremely high-temperature conditions).

**(FR):** La présente invention concerne un empilement optique ou une couche anti-décalage vers le rouge. La présente invention peut fournir un empilement optique ou une couche anti-décalage vers le rouge appliquée sur ce dernier, le phénomène dit de décalage vers le rouge n'étant pas induit même lorsque l'empilement optique est excité ou maintenu dans des conditions extrêmement difficiles (par exemple, des conditions de température extrêmement élevée).

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